



## Symposium on Direct Write, Optical, Ion and Electron Beam Lithography

This symposium features technical experts from Heidelberg Instruments, Nanoscribe, ZEISS, micro resist technology and Raith who will describe the spectrum of latest, state-of-the-art direct-write capabilities.

TU Delft and Kavli Nanolab Delft make modern nanofabrication capabilities available to the community; we also welcome researchers from industry and other universities.

9:00 - 9:15

### **Welcome and Introductions**

*TU Delft, Frank Dirne*

9:15 – 9:45

### **EBID (electron beam induced deposition)**

*TU Delft, Aya Mahgoub*

9:45 – 10:15

### **Gray Scale Lithography: Creating Complex 2.5D Structures in Thick Photoresist by Direct Laser Writing**

*Heidelberg Instruments, Christian Pies*

10:15 - 10:45

### **Latest Advances in Electron Beam Lithography and Process Metrology**

*Raith, Frank Nouvertné*

10:45 - 11:15

### **Coffee Break**

11:15 – 12:00

### **Direct Write Nanopatterning Using Multiple Ion Beams**

*Carl Zeiss Microscopy, Peter Gnauck*

12:00 – 12:45

### **Additive Manufacturing at the Micrometer Scale by Two-photon Polymerization**

*Nanoscribe, Jochen Zimmer*

12:45 – 14:00

### **Lunch Break**

14:00 - 14:45

### **Latest Highlights in Resist and Photopolymer Development for UV Direct Writing and E-beam Lithography**

*micro resist technology, Anja Voigt*

14:45 – 15:15

### **From Micro to Nano: Requirements and Solutions for High End Lithography**

*Heidelberg Instruments, Daniel-Alexander Braun*

15:15 – 15:45

### **FIB Nanofabrication: Advanced Applications and Key Benefits**

*Raith, Sven Bauerdick*

15:45 – 16:00

**Coffee Break**

16:00 – 18:00

**Process Clinic (open discussion about process related challenges)**

Lunch will be provided. During the Process Clinic we will serve free beer, wine, soft drinks and finger food. We are looking forward to have fruitful discussions with you about your actual challenges.

Please preregister at [Link](#).

**RAITH**  
NANOFABRICATION

**HEIDELBERG**  
INSTRUMENTS

**ZEISS**

 nanoscribe

micro resist  
technology